



*IPR \$*

AMENDMENT TRANSMITTAL LETTER				Docket No. SON-2769	
Application No. 10/603,689	Filing Date June 26, 2003	Examiner Saleha R. Mohammedulla		Art Unit 1756	
Applicant(s): Hidetoshi Ohnuma, et al					
Invention: EXPOSURE METHOD, MASK FABRICATION METHOD, FABRICATION METHOD OF SEMICONDUCTOR DEVICE, AND EXPOSURE APPARATUS					
<b>TO THE COMMISSIONER FOR PATENTS</b>					
Transmitted herewith is an amendment in the above-identified application.					
The fee has been calculated and is transmitted as shown below.					
<b>CLAIMS AS AMENDED</b>					
	Claims Remaining After Amendment	Highest Number Previously Paid	Number Extra Claims Present	Rate	
Total Claims	13	- 20 =		x	0.00
Independent Claims	2	- 3 =		x	
Multiple Dependent Claims (check if applicable) <input type="checkbox"/>					
Other fee (please specify): Submission of an Information Disclosure Statement (IDS)					
<b>TOTAL ADDITIONAL FEE FOR THIS AMENDMENT:</b>					
<input checked="" type="checkbox"/> Large Entity <input type="checkbox"/> Small Entity <input checked="" type="checkbox"/> No additional fee is required for this amendment. <input type="checkbox"/> Please charge Deposit Account No. _____ in the amount of \$ _____. A duplicate copy of this sheet is enclosed. <input type="checkbox"/> A check in the amount of \$ _____ to cover the filing fee is enclosed. <input type="checkbox"/> Payment by credit card. Form PTO-2038 is attached. <input checked="" type="checkbox"/> The Director is hereby authorized to charge and credit Deposit Account No. <u>18-0013</u> as described below. A duplicate copy of this sheet is enclosed. <input checked="" type="checkbox"/> Credit any overpayment. <input checked="" type="checkbox"/> Charge any additional filing or application processing fees required under 37 CFR 1.16 and 1.17.					
Dated: <u>August 3, 2005</u>					
Ronald P. Kananen Attorney Reg. No.: 24,104					
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PATENT APPLICATION  
Attorney Docket No.: SON-2769

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re the Patent Application of

Hidetoshi OHNUMA, *et al*

Group: 1756

Serial No. 10/603,689

Ex'r: Saleha R. Mohammedulla

Filed: June 26, 2003

Confirmation No. 2872

For: EXPOSURE METHOD, MASK FABRICATION  
METHOD, FABRICATION METHOD  
OF SEMICONDUCTOR DEVICE, AND  
EXPOSURE APPARATUS

**RESPONSE TO ELECTION OF INVENTION REQUIREMENT**

MS Non-Fee Amendment  
Commissioner for Patents  
PO Box 1450  
Alexandria, VA 22313-1450

Sir:

In response to the Official Action mailed on June 20, 2005, please amend the above-identified application as follows:

**Amendments to the claims begin on page 2 of this paper.**

**Remarks/Arguments begin on page 6 of this paper.**